

Notice of References Cited

Application/Control No.

09/838,513

Applicant(s)/Patent Under
Reexamination
CHEN ET AL.

Examiner

Julio J. Maldonado

Art Unit

2823

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.